



UNITED STATES PATENT and TRADEMARK OFFICE

UNDER SECRETARY OF COMMERCE FOR INTELLECTUAL PROPERTY AND
DIRECTOR OF THE UNITED STATES PATENT AND TRADEMARK OFFICE
WASHINGTON, D.C. 20231
WWW.USPTO.GOV

DEC - 2 2001

In re Application of:
Hoiman (Raymond) Hung
Serial No. 09/276,376
Filed: March 25, 1999
For: ENHANCEMENT OF SILICON
OXIDE ETCH RATE AND NITRIDE
SELECTIVITY USING HEXAFLUORO-
BUTADIENE OR OTHER HEAVY PER-
FLUOROCARBON

NOTICE OF WITHDRAWAL
FROM ISSUE UNDER
37 CFR 1.313 (b)

RECEIVED
DEC 9 2002
TC 1700

The above-identified application is withdrawn from issue after payment of the issue fee due to: reopening of prosecution. See 37 CFR 1.31(b).

The above-identified application is hereby withdrawn from issue.

The issue fee is refundable upon written request. If, however, the application is again found allowable, the issue fee can be applied toward payment of the issue fee in the amount identified on the new Notice of Allowance and Issue Fee Due upon request. This request and any balance due must be received on or before the due date noted in the new Notice of Allowance in order to prevent abandonment of the application.

Telephone inquiries should be directed to Randy Gulakowski at (703) 308-4333.

The above-identified application is being forwarded to the examiner for prompt appropriate action, including applicant of the new status of this application.

Jacqueline M. Stone

Jacqueline M. Stone, Director
Technology Center 1700
Chemical and Materials Engineering

09/276,376

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PATENT COUNSEL, MS/2061
Legal Affairs Dept. Applied Materials, Inc.
PO Box 450A
Santa Clara, CA 95052

cc: Allowed Files-PK3-910